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01/15/02

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

| APPL NUM | FILING DATE | CLASS | SUBCLASS | GAU | EXAMINER |
|----------|-------------|-------|----------|------|----------|
| 10047814 | 01/15/2002 | 438 | | 2812 | |

****APPLICANTS:** Kersch Alfred;

****CONTINUING DATA VERIFIED:**

**** FOREIGN APPLICATIONS VERIFIED:**

GERMANY 101 01 548.8 01/15/2001

PG-PUB DO NOT PUBLISH ☐

RESCIND ☐

Foreign priority claimed ☐ yes ☐ no

35 USC 119 conditions met ☐ yes ☐ no

Verified and Acknowledged Examiners's initials

ATTORNEY DOCKET NO

P2001,0011

TITLE : Reaction chamber for processing a substrate wafer, and method for operating the chamber

U.S. DEPT. OF COMM. / PAT. & TM. PTO-436L (Rev. 12-94)

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|---|-----------|---------------------------|-----------------------------|----------------------|
| NOTICE OF ALLOWANCE MAILED | | Assistant Examiner | CLAIMS ALLOWED | |
| | | | Total Claims | Print Claim for O.G. |
| ISSUE FEE | | Primary Examiner | DRAWING | |
| Amount Due | Date Paid | | Sheets Drwg. | Figs. Drwg. |
| <input type="checkbox"/> TERMINAL DISCLAIMER | | PREPARED FOR ISSUE | Application Examiner | |
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